



Suppression of Intrinsic Roughness in Suspended van der Waals Heterostructures

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Suspended graphene is known to show intrinsic corrugations on the nanometer scale [1] that have previously been measured to have a RMS roughness of $\sim 1.7 \text{ \AA}$ [2]. Intrinsic roughness is a suspected key source of scattering and thus a limiter of the carrier mobility in clean graphene samples [3, 4]. Suspending graphene flakes has proven to increase the electron mobility drastically compared to graphene supported on silicon oxide [5], as adverse effects on the mobility from the silicon oxide is eliminated. Similar improvements in mobility are obtained by encapsulating the graphene in hexagonal boron nitride (hBN) [6]. In this study we measured the intrinsic roughness of suspended exfoliated graphene flakes and compare to suspended graphene/hBN heterostructures, from electron diffraction patterns measured by diffraction studies in a transmission electron microscope. While we measure similar RMS roughness values for suspended graphene samples as that reported in literature, suspended graphene/hBN heterostructures show a strong suppression in the measured RMS roughness down to $\sim 0.2 \text{ \AA}$. Since the thickness dependence of the RMS roughness of hBN is reported to plateau at $\sim 1 \text{ \AA}$ for hBN thicker than $\sim 20 \text{ nm}$ [7], these results may lead to new fabrication strategies for obtaining high electron mobility graphene devices, since suspended heterostructures may be flatter than heterostructures placed on SiO_2 .

References:

- [1] J.C. Meyer et al, Nature 446, 60-63 (2007)
- [2] D. A. Kirilenko et al, PRB 84, 235417 (2007)
- [3] M. I. Katsnelson and A. K. Geim, Phil. Trans. R. Soc. 366, 195-204 (2008)
- [4] E.V. Castro et al, Phys. Rev. Lett. 105, 266601 (2010)
- [5] K.I. Bolotin et al, Solid State Communications 146, 351-355 (2008)
- [6] A.S. Mayorov et al, Nano Lett. 11, 2396-2399 (2011)
- [7] C. Dean et al (supplementary information), Nat. Nanotech. 5, 722-726 (2010)